

**VOLENTINE FRANCOS & WHITT, P.L.L.C.**

11951 Freedom Drive, Suite 1260

Reston, VA 20190 U.S.A.

Tel: 1.571.283.0720

Fax: 1.571.283.0740

Email: [iplaw@volentine.com](mailto:iplaw@volentine.com)Date: January 23, 2006To: Examiner Novacek  
U.S. Patent OfficeFax No: 571-273-8300

Ph. No:

From: Andrew J. Telesz, Jr.Subject: Serial No. 10/780,867  
Our Ref. No.: OKI.3900No. of Pages (including cover): 10.....  
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**CERTIFICATE OF TRANSMISSION BY FACSIMILE (37 CFR 1.8)**Applicant(s): **Kazuya Hizawa**

Docket No.

OKI.390C

Application No.

10/780,867

Filing Date

February 19, 2004

Examiner

C. Novacek

Group Art Unit

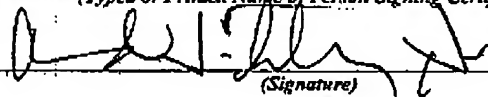
2822

Invention: **A METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE HAVING A METALLIC SILICIDE LAYER**

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**Request for Reconsideration***(Identify type of correspondence)*is being facsimile transmitted to the United States Patent and Trademark Office (Fax. No. 571-273-8300)

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Docket No.  
OKI.390CTRANSMITTAL LETTER  
(General - Patent Pending)

In Re Application Of: Kazuya Hizawa

Application No.  
10/780,867Filing Date  
February 19, 2004Examiner:  
C. NovacekCustomer No.  
20987Group Art Unit  
2822Confirmation No.  
1983

Title: A METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE HAVING A METALLIC SILICIDE LAYER

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Request for Reconsideration

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Dated: January 23, 2006

ANDREW J. TELESZ, JR.  
REG. NO. 33,581VOLENTINE FRANCOS & WHITT, P.L.L.C.  
11951 FREEDOM DRIVE, SUITE 1260  
RESTON, VA 20190  
TEL. NO. (571) 283-0720

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Serial No. 10/780,867

OKI.390C

Request for Reconsideration dated January 23, 2006

Via Facsimile 571-273-8300

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of

Kazuya Hizawa

Group Art Unit: 2822

Serial No.: 10/780,867

Examiner: C. Novacek

Filed: February 19, 2004

Confirm No.: 1983

For: A METHOD FOR FABRICATING A SEMICONDUCTOR DEVICE HAVING A  
METALLIC SILICIDE LAYER

## REQUEST FOR RECONSIDERATION

U.S. Patent and Trademark Office  
Customer Window, Mail Stop AF  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314

Date: January 23, 2006

Sir:

In response to the Final Office Action dated November 8, 2005, the following  
remarks are respectfully submitted in connection with the above-identified application.

Remarks/Arguments begin on page 2 of this paper.

Page 1 of 7

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